

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Junji FUJIKAWA et al

Art Unit:

S. N.

Examiner:

International S.N.: PCT/JP00/06038

#9

Filed:

International Filing Date: 6 September 2000

For: HALFTONE PHASE SHIFT PHOTOMASK,
AND HALFTONE PHASE SHIFT PHOTOMASK
BLANK FOR THE FABRICATION OF THE SAME

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Please make the following amendments to this application
prior to examination thereof:

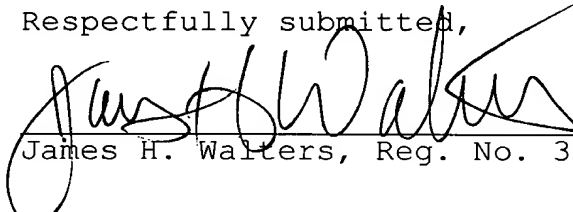
In the Drawings:

Please amend FIGS. 1-3, 7 and 8 as indicated in red on the
drawing sheets attached herewith.

REMARKS

The above amendments are submitted to place the application
into a format consistent with U.S. practice.

Respectfully submitted,


James H. Walters, Reg. No. 35,731

802
DELLETT AND WALTERS
Suite 1101
310 S.W. Fourth Avenue
Portland, Oregon 97204 US
(503) 224-0115
DOCKET: A-398

Express Mail #EL719795338US.

09830598-042701

~~FIG. 1~~

FIG. 1 (a)

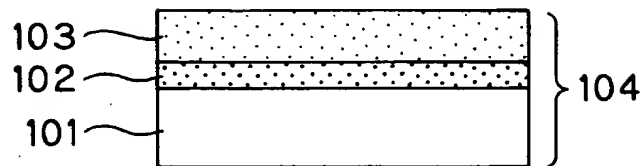


FIG. 1 (b)

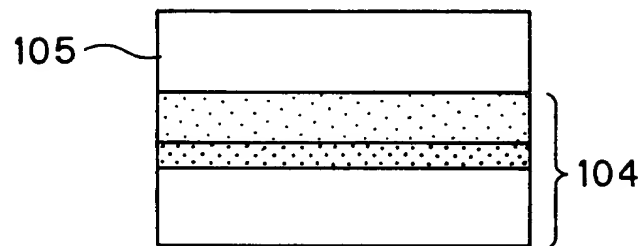


FIG. 1 (c)

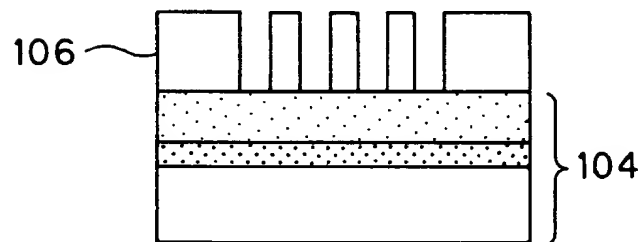
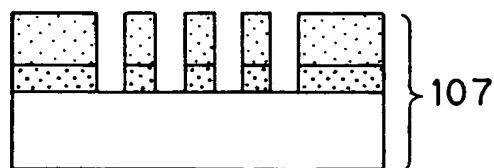


FIG. 1 (d)



~~FIG. 2~~

FIG. 2 (a)

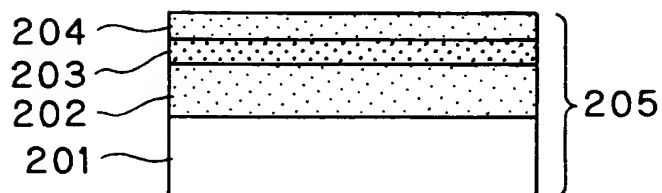
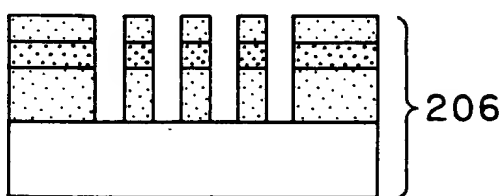


FIG. 2 (b)



~~FIG. 3~~

FIG. 3 (a)

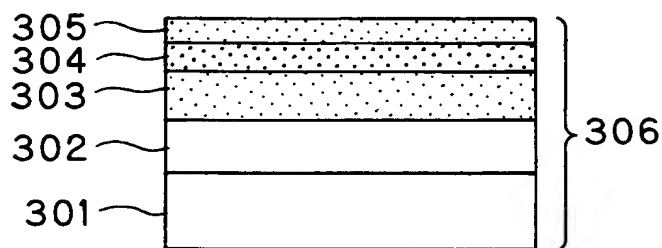
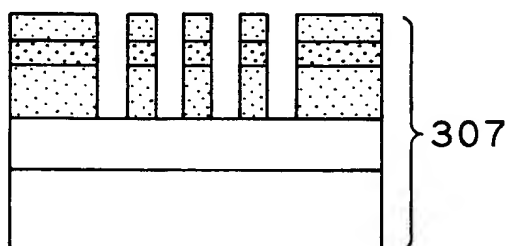


FIG. 3 (b)



~~FIG. 7~~

FIG. 7 (a)

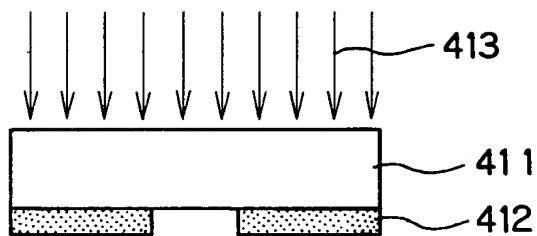


FIG. 7 (b)



FIG. 7 (c)

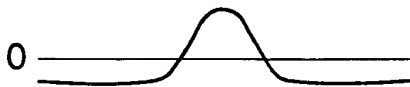
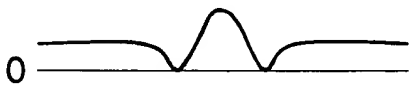


FIG. 7 (d)



~~FIG. 8~~

FIG. 8 (a)

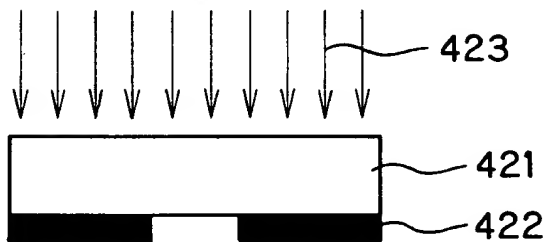


FIG. 8 (b)

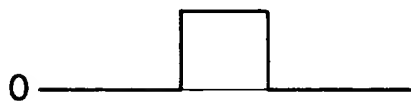


FIG. 8 (c)



FIG. 8 (d)

